

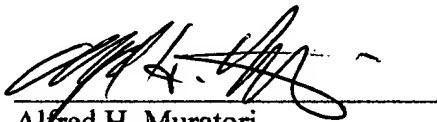
Applicant would like to thank the Examiner for the indication of allowable subject matter in Claims 6, 20-22 and 27. Claims 6 and 20-22 have been rewritten in independent form to include all of the limitations of original claim 1.

Claims 1-4, 7-19, 23-26, and 28-33 were rejected under 35 USC 102(b) or 35 USC 103(a) in view of Wadley et al. This rejection is respectfully traversed. In Wadley et al. an electron beam is impinged upon a solid material, to thereby vaporize the material into a precursor form (suspension). In doing so, the energy source is applied to "activate" the material, which results in the vaporized material being "fed" to the gas stream. This is distinctly different from amended claim 1 wherein precursor material is first fed into a localized environment of the energy source and the energy source activates the precursor material within gasses. The material of Wadley et al. is activated prior to being "within gasses." Further, Claim 1 also requires that the gasses are directed along a first path, not that the precursor material itself is directed along a first path as in Wadley et al. The amendment to Claim 1 was intended to further define this feature of the present invention.

For the above reasons, it is hereby believed that the claims of record are allowable over the prior art and early indication of the same is requested. As this request is within the fourth month of the response period, the commissioner is hereby authorized to charge \$120 one month extension fee to deposit account 501231.

Respectfully submitted,

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## Appendix B

Because CCVD generally uses solutions, a significant advantage of this technology is that it allows rapid and simple changes in dopants and stoichiometries which eases deposition of complex films. The CCVD technique generally uses inexpensive, soluble precursors. The Nanomiser™ as described in co-pending U.S. Patent Applications No. 08/691,853, filed 8/2/96, (now U.S. Patent No. 5,997,956), and U.S. Patent Applications Nos. 09/293,867, (now abandoned) 09/293,028 (now abandoned) and 09/293,030, (now U.S. Patent No. 6,132,653) all filed 4/16/99 as divisionals of U.S. Patent Application No. 08/691,853, breaks the liquid into micron or even sub-micron sized droplets. These patent applications are all owned by the assign of the present invention and are hereby incorporated by reference. In addition, precursor vapor pressures generally do not play a role in CCVD because the dissolution process provides the energy for the creation of the necessary ionic constituents. By adjusting solution concentrations and constituents, a wide range of stoichiometries can be deposited quickly and easily. Additionally, the CCVD process allows both chemical composition and physical structure of the deposited film to be tailored to the requirements of the specific application.